Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4728	((216/41,51,95-97,99) or (438/735,736,745,753,756,757)). CCLS.	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L3	88721	(si OR silicon\$4) NEAR20 etch\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L4	15035	L3 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L5	824	L4 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L6	385	L5 AND (stress\$4 OR strain\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L7	158	L6 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L8	101	L7 AND (anisotropic\$4 NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L9	3	L1 AND L8	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:49
L10	11963	(si OR silicon\$4) NEAR20 etch\$4 NEAR20 wet\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L11	8266	L10 AND (etch\$4 NEAR20 mask\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L12	3286	L11 AND ((etch\$4 NEAR20 mask\$4) NEAR20 nitride\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:51
L13	2274	L12 AND ((etch\$4 NEAR20 mask\$4) NEAR20 oxide\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:51
L14	243	L13 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:51
L15	28	L1 AND L14	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:50
L16	1714	(si OR silicon\$4) NEAR20 etch\$4 NEAR20 wet\$4	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:50
L17	475	L16 AND (etch\$4 NEAR20 mask\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:51
L18	121	L17 AND ((etch\$4 NEAR20 mask\$4) NEAR20 nitride\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:51
L19	76	L18 AND ((etch\$4 NEAR20 mask\$4) NEAR20 oxide\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:52

L20	1	L19 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/30 11:52
S5	88438	(si OR silicon\$4) NEAR20 etch\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:04
S18	14996	S5 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 11:43
S21	822	S18 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:06
S22	2	S21 AND (nitrid\$4 NEAR20 (stress\$4 OR strain\$4) NEAR20 relax\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 09:15
S23	20	S21 AND ((stress\$4 OR strain\$4) NEAR20 relax\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 14:59
S24	6716	((silicon OR Si) NEAR20 etch\$4) AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 15:09
S25	822	S24 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 15:10
S26	385	S25 AND (stress\$4 OR strain\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 16:40
S27	145	S26 AND ((stress\$4 OR strain\$4) NEAR20 (reduc\$5 OR relief\$4 OR relax\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/21 16:18
S28	347	S25 AND ((stress\$4 OR strain\$4) NEAR20 crack\$4 OR defect\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 16:48
S29	30	S25 AND ((stress\$4 OR strain\$4) NEAR20 crack\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/21 17:02
S30	88721	(si OR silicon\$4) NEAR20 etch\$4	US-PGPUB; USPAT	OR	OFF	2005/11/29 09:15
S31	15035	S30 AND (oxide\$4 NEAR20 thickness\$4) AND (nitride\$4 NEAR20 thickness\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 09:15
S32	824	S31 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:53
S33	122	S32 AND (nitrid\$4 NEAR20 (stress\$4 OR strain\$4))	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:18
S34	42	S33 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:18
S35	4	S34 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6) NEAR20 (groove\$4 OR trench\$4 OR open\$4))	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:59

S36	50	(("5616401") or ("6057241") or ("6720226") or ("4925807") or ("6174792") or ("6908858") or ("4951063") or ("5240559") or ("5275695") or ("5275695") or ("5348906") or ("5604371") or ("5665641") or ("5754619") or ("5905005") or ("5920780") or ("6981308") or ("6004840") or ("6081308") or ("6128363") or ("4371407") or ("4445967") or ("4839708") or ("5204210") or ("5259924") or ("5362350") or ("5362575") or ("5364743") or ("5382823") or ("5395802") or ("5420079") or ("5498566") or ("5506168") or ("5512509") or ("5539256") or	USPAT	OR	OFF	2005/11/29 10:53
		("5541023") or ("5599722") or ("5627099") or ("5677229") or ("5677090") or ("5789769") or ("5804504") or ("5821402") or ("5848120") or ("5905044") or ("6013573") or ("6037083") or ("6121110")).PN.				
S37	0	S33 AND S36	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:53
S38	1	S32 AND S36	US-PGPUB; USPAT	OR	OFF	2005/11/29 10:53
S39	385	S32 AND (stress\$4 OR strain\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:18
S40	158	S39 AND ((stress\$4 OR strain\$4) NEAR20 (relax\$6 OR relie\$6 OR reduc\$6))	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:22
S41	101	S40 AND (anisotropic\$4 NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/29 11:23
S42	1	("5738757").PN.	USPAT	OR	OFF	2005/11/30 08:53
S43	11963	(si OR silicon\$4) NEAR20 etch\$4 NEAR20 wet\$4	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:05
S44	8266	S43 AND (etch\$4 NEAR20 mask\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:05
S45	4865	S44 AND ((etch\$4 NEAR20 mask\$4) NEAR20 (nitride\$4 OR oxide\$4))	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:06
S46	704	S45 AND ((hydroxide\$4 OR alkali\$4) NEAR20 etch\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:07
S47	3286	S44 AND ((etch\$4 NEAR20 mask\$4) NEAR20 nitride\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:07
S48	2274	S47 AND ((etch\$4 NEAR20 mask\$4) NEAR20 oxide\$4)	US-PGPUB; USPAT	OR	OFF	2005/11/30 09:07

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C:\Documents and Settings\echen\My Documents\EAST\Workspaces\Anisotropic Wet Etching of Silicon.wsp

S49	243	S48 AND ((hydroxide\$4 OR	US-PGPUB;	OR	OFF	2005/11/30 09:07
		alkali\$4) NEAR20 etch\$4)	USPAT			
		("5738757").URPN.				